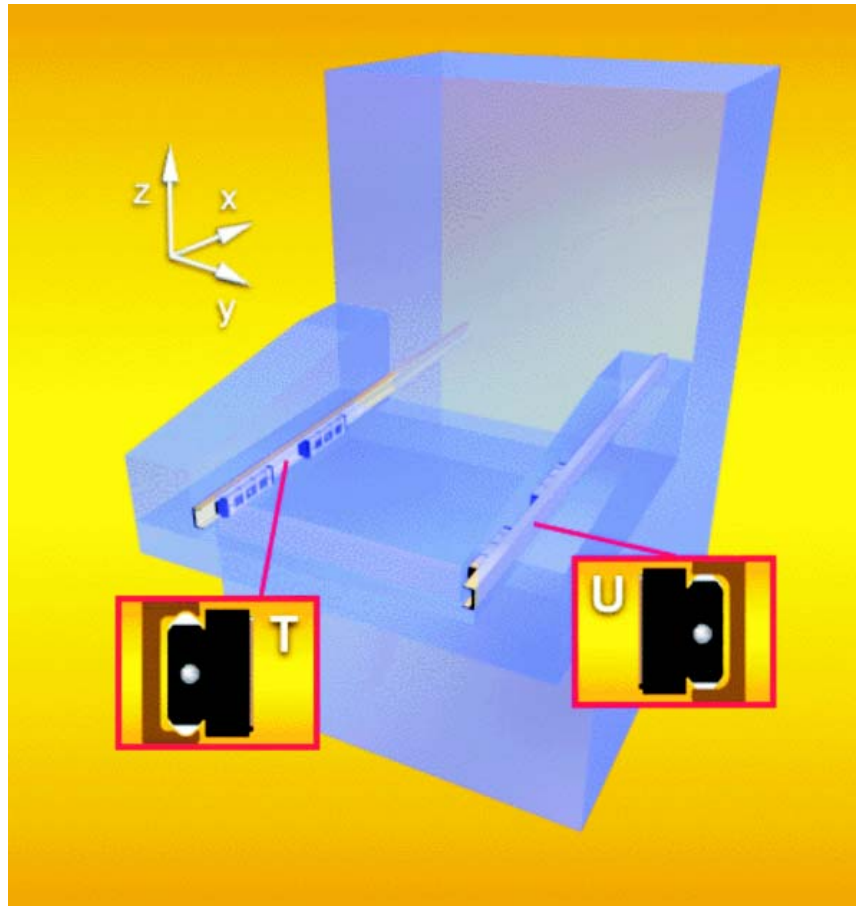


## EXPOSURE UNIT

In the photographic application below, the pair of T+U-rails move the exposed plates towards the development device.

A linear system that absorbs large parallelism errors is needed since the welded mounting structure offers very low precision.

In addition, smooth and silent movement with no lubrication in order to maintain the very clean environment is required.



Application data	X Axis	Y Axis	Z Axis
Weight of moving part [N]	1000		
Dimensions of moving part [mm]	800x800		
Stroke [mm]	800		
Speed [m/s max]	1.5		
Frequency of movement [cycles/min]	30		
Precision of movement [mm/m]	0.1		
Environment conditions	Completely dust free		
Other special requirements	No lubrication		
Product used	TLV28-1680/2/NT28 ULV28-1680/2/NU28		